

2152

Docket No.: 5199/Consilium/MBE

PATENT/OFFICIAL

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of

Yueshian T. CHI et al.

Serial No. 09/725,908

Filed: November 30, 2000



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Group Art Unit: 2152

Examiner:

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SEP 24 2002  
Technology Center 2100

For: DYNAMIC SUBJECT INFORMATION GENERATION IN MESSAGE SERVICES OF  
DISTRIBUTED OBJECT SYSTEMS

**SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT**

Honorable Commissioner for Patents  
Washington, D.C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached form PTO-1449. It is respectfully requested that the documents be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

This submission does not constitute a representation that a search has been made or that no better art exists and does not constitute an admission or representation that any of the listed documents is material or constitutes prior art. If it should be determined that any of the listed documents does not constitute prior art under the United States law, Applicants reserve the right

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to present to the Office the relevant facts and law regarding the appropriate status of such document.

No certification or fee is believed to be required. However, the Commissioner is hereby authorized to charge any additional fees should any be required for this submission, or credit any overpayment to deposit account no. 08-0219.

Respectfully submitted,

HALE AND DORR LLP

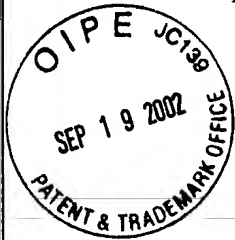
A handwritten signature in black ink, appearing to read "Scott M. Alter". The signature is fluid and cursive, with the first name "Scott" being more prominent than the last name "Alter".

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**INFORMATION DISCLOSURE  
CITATION IN AN  
APPLICATION**



(PTO-1449)

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**U.S. PATENT DOCUMENTS**

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						Yes	No
	61-171147	08/01/86	Japan				X
	6-184434	07/05/94	Japan				X
	0 621 522 A2	10/26/94	Europe			X	
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	February 1984. "Method and Apparatus of in Situ Measurement and Overlay Error Analysis for Correcting Step and Repeat Lithographic Cameras." <i>IBM Technical Disclosure Bulletin</i> , pp. 4855-4859.
	October 1984. "Method to Characterize the Stability of a Step and Repeat Lithographic System." <i>IBM Technical Disclosure Bulletin</i> , pp. 2857-2860.

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DATE CONSIDERED

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						Yes	No
	0 747 795 A2	12/11/96	Europe			X	
	10-173029	06/26/98	Japan				X
	0 895 145 A1	02/03/99	Europe			X	
	11-126816	05/11/99	Japan				X


**OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

	Schmid, Hans Albrecht. 1995. "Creating the Architecture of a Manufacturing Framework by Design Patterns." Austin, Texas: OOPSLA.
	Baliga, John. July 1999. "Advanced Process Control: Soon to be a Must." Cahners Semiconductor International. <a href="http://www.semiconductor.net/semiconductor/issues/issues/1999/jul99/docs/feature1.asp">www.semiconductor.net/semiconductor/issues/issues/1999/jul99/docs/feature1.asp</a>


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				APPLICANT Yueshian T. CHI et al.			
				FILING DATE November 30, 2000		GROUP 2152	
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	6,226,792	05/01/01	Goiffon et al.			10/14/98	
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						Yes	No
	11-135601	05/21/99	Japan				X
	WO 00/05759	02/03/00	WO			X	
	WO 00/35063	06/15/00	WO			X	
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	July 5, 2001. "Motorola and Advanced Micro Devices Buy ObjectSpace Catalyst Advanced Process Control Product for Five Wafer Fabs." Semiconductor FABTECH. <a href="http://www.semiconductorfabtech.com/industry.news/9907/20.07.shtml">www.semiconductorfabtech.com/industry.news/9907/20.07.shtml</a>						
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	Sonderman, Thomas. 2002. "APC as a Competitive Manufacturing Technology: AMD's Vision for 300mm." AEC/APC.						
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	6,263,255	07/17/01	Tan et al.			05/18/98	
	6,292,708	09/18/01	Allen et al.			06/11/98	
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	6,303,395	10/16/01	Nulman			06/01/99	
	6,345,315	02/05/02	Mishra			08/12/98	
	6,366,934	04/02/02	Cheng et al.			06/02/99	
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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	WO 00/79355 A1	12/28/00	WO			X	
	2001-76982	03/23/01	Japan				X
	WO 01/33501 A1	05/10/01	WO			X	
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